

CVD reactor with a supporting ring, and a supporting ring
for a substrate

Abstract

The invention relates to a supporting ring (20), which is arranged in a CVD reactor and is part of a bearing arrangement which is intended for the mounting of a substrate (10) and is arranged above a susceptor and is supplied with heat by the susceptor, wherein it is essential that the heat is transferred from the susceptor to a radially outer region (21) or to a radially inner region (22) of the supporting ring (20) via an annular web (33) of the supporting ring (20).

FIG. 4